

What is Claimed is:

- [c1] 1. An apparatus for holding a substrate, said apparatus comprising:
a pocket adapted to hold said substrate, wherein said pocket has an inner edge and a lower surface; and
a plurality of projections extending radially inward from said inner edge, wherein said projections have a beveled edge, such that an acute angle occurs between said lower surface and said beveled edge, and wherein said projections reduce an area of contact between said inner edge and said substrate.
- [c2] 2. The apparatus of claim 1, wherein said apparatus comprises a susceptor for a substrate.
- [c3] 3. The apparatus of claim 1, wherein said projections have a "C" shape.
- [c4] 4. The apparatus of claim 1, wherein said projections maintain a gap between a sidewall of said substrate and said inner edge.
- [c5] 5. The apparatus of claim 1, wherein said acute angle comprises an angle between 80 and 85 degrees.
- [c6] 6. The apparatus of claim 1, wherein said projections prevent said substrate from moving within said pocket.
- [c7] 7. An apparatus for holding a substrate, said apparatus comprising:
a pocket adapted to hold said substrate, wherein said pocket has an inner edge; and
a plurality of projections extending radially inward from said inner edge, wherein said projections have a beveled edge.
- [c8] 8. The apparatus in claim 7, wherein an acute angle occurs between a lower surface of said pocket and said beveled edge.
- [c9] 9. The apparatus in claim 7, wherein said projections reduce an area of contact between said inner edge and said substrate.
- [c10] 10. The apparatus of claim 7, wherein said apparatus comprises a susceptor for

a substrate.

- [c11] 11. The apparatus of claim 7, wherein said projections have a "C" shape.
- [c12] 12. The apparatus of claim 7, wherein said projections maintain a gap between a sidewall of said substrate and said inner edge.
- [c13] 13. The apparatus of claim 8, wherein said acute angle comprises an angle between 80 and 85 degrees.
- [c14] 14. The apparatus of claim 7, wherein said projections prevent said substrate from moving within said pocket.
- [c15] 15. A susceptor for holding a wafer, said susceptor comprising:
a pocket adapted to hold said wafer, wherein said pocket has an inner edge; and
a plurality of projections extending radially inward from said inner edge, wherein said projections have a beveled edge.
- [c16] 16. The susceptor in claim 15, wherein an acute angle occurs between a lower surface of said pocket and said beveled edge.
- [c17] 17. The susceptor of claim 16, wherein said acute angle is between 80 and 85 degrees.
- [c18] 18. The susceptor of claim 17, wherein said projections have a "C" shape.